



Sheet 1 of 1

FORM PTO-149	Atty. Docket No.: I69.12-0556	Application No.: <del>10/673,795</del> 10/673,795
LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT	First Named Inventor: Kalman Pelhos	
	Filing Date: September 29, 2003	Group Art: 2652

#### U.S. PATENT DOCUMENTS

Examiner Initials	Document No.	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Documents
AA			
AB			

#### FOREIGN PATENT DOCUMENTS

		Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Documents	Translation Yes No
ST	AC	WO8007250	06-14-1994	Hitachi Ltd	No
SD	AD	2002042326	07-19-2000	KYOCERA CORP	Yes

#### OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

AE	Kiwamu Tanahashi, Yuzuru Hosoe, Masaaki Futamoto; <i>Magnetic Anisotropy and Microstructure of Obliquely Evaporated Co/Cr Thin Films</i> ; July 24, 1995; pgs. 265 - 272.
AF	Y.F. Zheng and J.P. Wang; <i>Control of the Tilted Orientation of CoCrPt/Ti thin film media by collimated sputtering</i> ; May 15, 2002; V931 pgs. 0007 - 0009.
AG	M.J. Hadley, R. Atkinson, R.J. Pollard; <i>Magnetic Properties of Co Films Deposited Onto Obliquely Sputtered Ta Underlayers</i> ; January 31, 2002.
AH	Dieter Weller and Andreas Moser; <i>Thermal Effect Limits in Ultrahigh-Density Magnetic Recording</i> ; November 1999; volume 35, pgs. 4423 - 4439.
AI	R.D. McMichael, C.G. Lee, J.E. Bonevich, P.J. Chen, W. Miller, and W.F. Egelhoff, Jr; <i>Strong Anisotropy in Thin Magnetic Films Deposited on Obliquely Sputtered Ta Underlayers</i> ; volume 88, No. 9, pgs. 5296 - 5299.0
AJ	A. Hagemeyer, H.J. Richter, H. Hibst, V. Maier and L. Marosi; <i>Crystallographic Texture and Morphology of Obliquely Deposited Co-Cr Magnetic Thin Films on Flexible Polymeric Substrates</i> ; August, 10, 1993; pgs. 199 - 202.
AK	T. Hikosaka, Y. Tamaka, T. Sonoda, and R. Nishikawa; <i>Cr Underlayer's Effect on the Magnetic and Crystalline Properties of Co Alloy Film</i> ; June 1988; volume 3, No. 6, pgs. 423 - 424.
AL	J.C. Lodder; <i>Magnetic Thin Films for High-Density Recording</i> ; 1996; pgs 474 - 483

EXAMINER:       

DATE CONSIDERED: 4/20/05

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

FORM PTO-1449		Atty. Docket No.: 169.12-0582	Application No.: 10/673,795
<p style="text-align: center;"> <b>LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT</b> </p> <p style="text-align: center;">JUL 12 2004</p> <p style="text-align: center;">SEARCHED INDEXED SERIALIZED FILED</p>		First Named Inventor: Kalman Pelhos	
		Filing Date: September 29, 2003	Group Art: 1762

## U.S. PATENT DOCUMENTS

Examiner Initials	Document No.	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Documents
AA	US 2003/0019745 A1	01-30-2003	Wang et al.
AB			
AC			
AD			
AE			
AF			
AG			
AH			

## FOREIGN PATENT DOCUMENTS

		Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Documents	Translation Yes No
	AI	1,213,055	11-18-1970	Irwin William Fischbein	Yes
	AJ	5-101385	04-23-1993	Uchiyama Yoichi	Yes and Abstract
	AK	2002020857	01-23-2002	Segawa Masaru	Abstract only

## OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

AL	
AM	
AN	

EXAMINER:

DATE CONSIDERED: 4/20/05

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FORM PTO-1449	Atty. Docket No.: I69.12-0582	Application No.: 10/673,795
LIST OF PATENTS AND PUBLICATIONS FOR APPLICANTS INFORMATION DISCLOSURE STATEMENT		First Named Inventor: Kalman Pelhos et al.
	Filing Date: September 29, 2003	Group Art: 1762

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Examiner Initials	Document No.	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Documents
AA	US2003/0019745	01-30-2003	Wang et al.
AB			

## FOREIGN PATENT DOCUMENTS

		Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Documents	Translation Yes No
AC	EP05280473		02-05-1995	Sony Corp.	YES
AD	EP08298096		10-21-1996	Ricoh Co Ltd.	YES
AE	EP06131571		12-01-1996	Hitachi LTD.	YES

## OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

AF	PCT/US03/30489, <i>Notification of Transmittal of the International Search Report or the Declaration</i> , August 2004, pages 1-3.
AG	PCT/US03/30489, <i>International Search Report</i> , August 2004, pages 1-4.
AH	McMichael et al., <i>Strong Anisotropy in Thin Magnetic Films Deposited on Obliquely Sputtered Ta Underlayers</i> , November 2000, pages 5296-5299.

EXAMINER: *DRE*DATE CONSIDERED: *4/20/05*

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<b>FORM PTO-1449</b>		Atty. Docket No.: I69.12-0582	Application No.:
<b>LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT</b>		First Named Inventor: Kalman Pelhos et al.	
		Filing Date: Herewith	Group Art:

**U.S. PATENT DOCUMENTS**

Examiner Initial	Document No.	Date	Name	Class	Sub Class	Filing Date If Appropriate
AA	5,198,090	03/30/1993	Galicki et al.	204	298.11	
AB	5,804,046	09/08/1998	Sawada et al.	204	298.11	
AC						
AD						
AE						
AF						
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AH						
AI						
AJ						
AK						

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		Document No.	Date	Country	Class	Sub Class	Translation Yes No
AL	07-141610		02/06/1995	Japan			No
AM	09-212855		15/08/1997	Japan			No
AN	58-128023		30/07/1983	Japan			No
AO	2002-020864		23/01/2002	Japan			No

**OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)**

AP	Y. F. Zheng and J. P. Wang and V. Ng; Control of the tilted orientation of CoCrPt/Ti thin film media by collimated sputtering; May 15, 2002; Journal of Applied Physics; Volume 91, Number 10
AQ	
AR	

EXAMINER: [initials] DATE CONSIDERED: 4/24/05

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.